



Sheet 1 of 1

Subst. Form PTO-1449

Docket Number (Optional)

SAM-0313

Application Number

10/081,661

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

Applicant

Soo-geun Lee, et al.

Filing Date

2-22-02

Group Art Unit

2812

(Use several sheets if necessary)

U. S. Patent Documents

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB	6,559,520	5/6/03	Matsuki, et al.	257	642	4/25/02
	AC	6,514,880	2/4/03	Matsuki, et al.	438	780	4/6/01
	AD	6,455,445	9/24/02	Matsuki	438	789	3/28/01
	AE	6,432,846	8/13/02	Matsuki	438	790	10/18/00
	AF	6,410,463	6/25/02	Matsuki	438	790	10/18/00
	AG	6,383,955	5/7/02	Matsuki, et al.	438	790	6/7/99
	AH	6,352,945	3/5/02	Matsuki, et al.	438	778	6/7/99
	AI	6,057,239	5/2/00	Wang, et al.	438	689	12/17/97
	AJ	01/0046778	11/29/01	Wang, et al.	H01L	21/302	3/22/00
	AK						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
	AL							
	AM							
	AN							
	AO							
	AP							
	AQ							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	AR	Jiang, P., et al., "Trench Etch Processes for Dual Damascene Patterning of Low-k Dielectrics, J. Vac. Sci. Technology, A 19(4), Jul/Aug 2001, p. 1388-1391.
	AS	
	AT	

EXAMINER

DATE CONSIDERED

3-12-4

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy with next communication to applicant.